MAM2025
MARCH 24-27 • LEUVEN (BELGIUM)

(as of 23/01/2025)

MONDAY MARCH 24, 2025 - WORKSHOP

08:30-09:00	**Registration**	
09:00-09:15	**Opening - Christopher J. Wilson**	
09:15-09:55	**Anand Murthy** (Lam, USA) The Metallization Routing to Two Trillion Dollars	I
09:55-10:35	**Henrik H. Sønsteby** (University of Oslo, Norway) From stamp to wafer - How complex ALD processes become exponentially harder to control on fab-friendly scale	I
10:35-11:05	**Coffee Break**	
11:05-11:45	**Robert Clark** (TEL, USA) Selective and Self-Limited Process Technologies to Enable Ångstrom Scale Integrated Circuits	I
11:45-12:25	**Mikko Ritala** (University of Helsinki, Finland) ALD and AS-ALD of Metallic Films with New Precursors and Approaches	I
12:25-13:25	**Lunch**	
13:25-14:05	**Chiyu Zhu** (ASM, Finland) Time for ALD Metals: Enabling the next generation of leading-edge devices	I
14:05-14:45	**Hubert Renevier** (LMGP, Univ. Grenoble Alpes, CNRS, Grenoble-INP, France) In situ study of the synthesis of lamellar metal chalcogenides by alternating deposition of organic & inorganic molecules	I
14:45-15:15	**Coffee Break**	
15:15-15:55	**Cara-Lena Nies** (Tyndall National Institute, Ireland) Understanding and predicting interconnect metal deposition and morphology from atomic scale simulations	I
15:55-16:35	**Mark Saly** (Applied Materials, USA) Next Generation Microelectronics Devices Enabled by Atomic Layer Deposition	I
16:35-17:35	Panel discussion	